

B<sup>1</sup>  
cond.

wherein the transparent conductive film has a work function of 4.9 to 5.5 eV, a surface roughness of 1 to 10 nm and a specific resistance of  $1.6 \times 10^{-4} \Omega \cdot \text{cm}$  or less.

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REMARKS

It is requested that the above amendment be entered to correct a typographical error in the claim.

Respectfully submitted,

01/28/02

Date

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A marked up version of rewritten amended claims is provided as follows:

## IN THE CLAIMS

Please amend claim 6 as follows:

6. (Amended) A method of producing a substrate with a transparent conductive film, comprising:

providing a transparent substrate; and

ion plating a transparent conductive film on a surface of said transparent substrate by using indium-tin oxide which is a mixture of tin oxide and indium oxide as a material to be vaporized,

wherein the transparent conductive film has a work function of 4.9 to 5.5 eV, a surface roughness of 1 to 10 nm and a specific resistance of  $1.6 \times 10^{-4} \Omega \cdot \text{cm}$  or less.